



JPW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

IZUMI, Katsutoshi, et al.

Group Art Unit: **2823**

Serial No.: **10/708,593**

Examiner: **Michelle ESTRADA**

Filed: **March 12, 2004**

P.T.O. Confirmation No.: **2592**

For: **METHOD FOR MANUFACTURING BURIED INSULATING LAYER
TYPE SINGLE CRYSTAL SILICON CARBIDE SUBSTRATE (AS AMENDED)**

RESPONSE TO THE RESTRICTION REQUIREMENT
DATED January 11, 2005

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Date: February 7, 2005

Sir:

This paper is submitted in response to the Official Action dated **January 11, 2005**.

In the Action, restriction is required between Group (I), Claims 1-6; and Group (II),
Claims 7-15.

Applicants hereby elect the subject matter of Group (I), Claims 1-6 for prosecution in this application. This election is made without traverse, it being understood that the applicants' rights to the filing of a divisional application directed to the non-elected subject matter under 35 USC 120 and 35 USC 121 are retained.

In the event that this paper is not timely filed, applicants hereby petition for an appropriate extension of time. The fee for any such extension may be charged to our Deposit Account No. 01-2340.

RESPONSE TO THE RESTRICTION REQUIREMENT

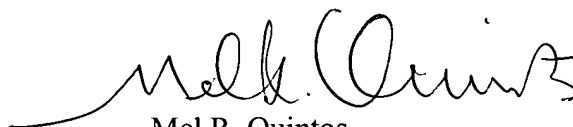
filed on February 7, 2005

U.S. Patent Application No. 10/708,593

In the event any additional fees are required in connection with this response, please
charge our Deposit Account No. 01-2340.

Respectfully submitted,

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PATENT TRADEMARK OFFICE

Enclosure: Preliminary Amendment